

Application No.: 10/647,347Docket No.: 2328-050A**Amendments to the Claims:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

Claims 1-25 (canceled).

Claim 26 (original): A method of controlling the plasma flux distribution on a workpiece of an inductive plasma processor including a plasma excitation coil having a center axis and plural parallel connected windings adapted to be driven by an excitation source, the plural parallel connected windings being concentric with the axis so an exterior winding of the coil surrounds the remainder of the coil, the method comprising positioning the exterior winding relative to the remainder of the coil so the plasma density incident on the workpiece has a predetermined desired relationship.

Claim 27 (original): The method of claim 26 wherein the positioning step includes turning the exterior winding and another winding of the coil relative to each other about the axis.

Claim 28 (new): The method of claim 27, wherein the exterior winding is turned relative to the another winding to assist in controlling azimuthal electric field distribution and azimuthal plasma density distribution of the processor.

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Claim 29 (new): The method of claim 28, wherein the method is performed on a plurality of different processors of the same type having differing azimuthal electric field and plasma density distributions from processor to processor and the exterior winding of each particular processor is turned relative to the remainder of the coil of the particular processor until tests indicate optimum uniform plasma distribution is achieved in each processor.

Claim 30 (new): The method of claim 27, wherein the exterior winding is moved relative to another winding to assist in controlling azimuthal electric field distribution and azimuthal plasma density distribution of the processor.

Claim 31 (new): The method of claim 26, wherein the method is performed on a plurality of different processors of the same type having differing azimuthal electric field and plasma density distributions from processor to processor and the exterior winding of each particular processor is moved relative to the remainder of the coil of the particular processor until tests indicate optimum uniform plasma distribution is achieved in each processor.